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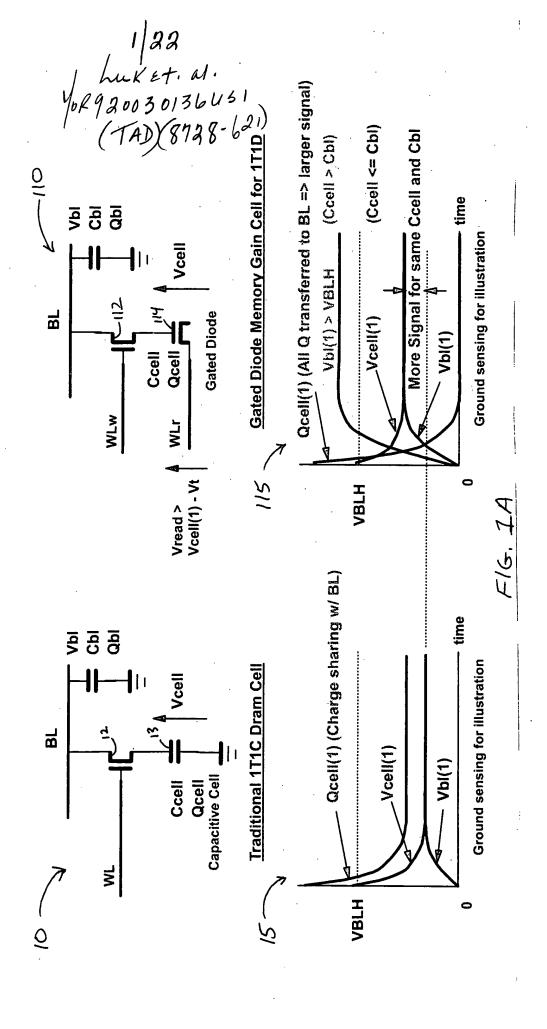
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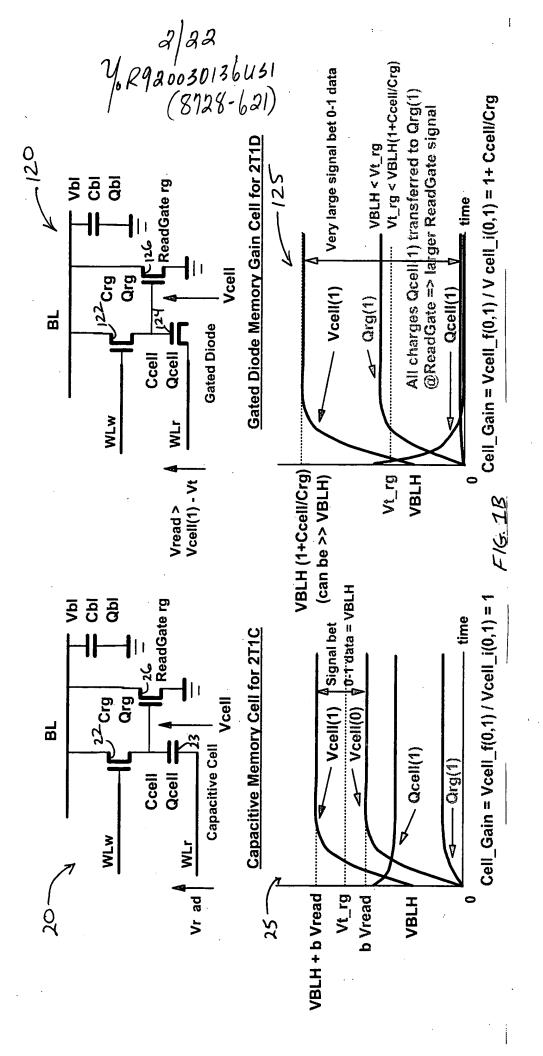
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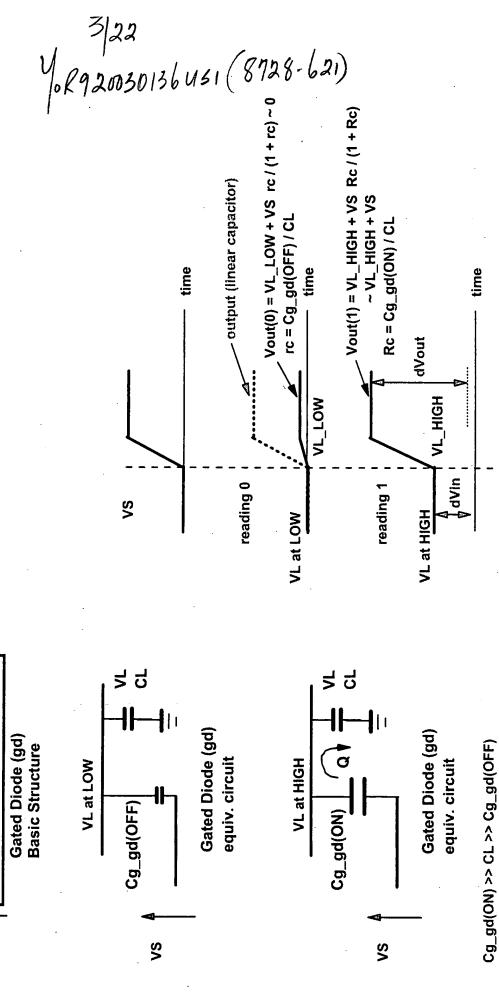
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O

Cg\_gd

S

Typically, Cg\_gd(OFF) : CL : Cg\_gd(ON) = 1 : 10 : 100

F/G. 24

Gain = 
$$1 + Rc - (Vt_gd / Vg_i) Rc \sim 1 + Rc$$
 complete charge transfer (for section =  $(1 + Vs / Vg_i) Rc / (1 + Rc)$  constrained charge transfer (for section =  $(1 + Vs / Vg_i) Rc / (1 + Rc)$  constrained charge transfer (for section =  $(1 + Vs / Vg_i) Rc / (1 + Rc)$  constrained charge transfer (for section =  $(1 + Vs / Vg_i) Rc / (1 + Rc)$  constrainted constrainted

complete charge transfer (for small Rc) constrained charge transfer (large Rc)

Read

Cg\_rg

Gate

Vg\_f

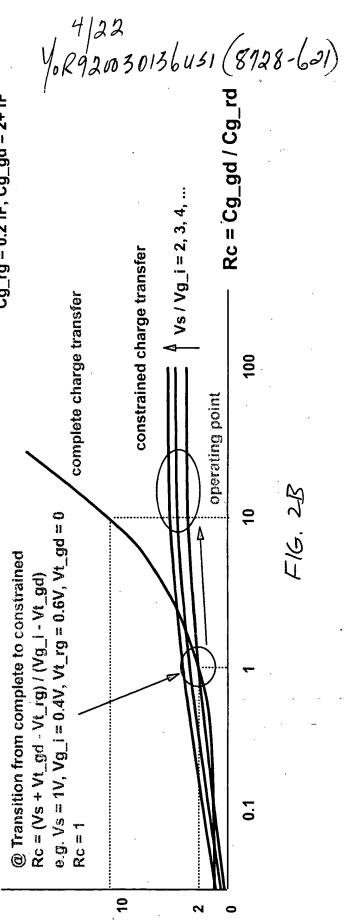
Cell (gd)

**Gated Diod** 

**e** 

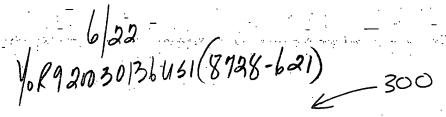
- 10 - 20 x Qmin charge reserved in Gate Diode for SER protection Cg\_rg = 0.2 fF, Cg\_gd = 2+ fF

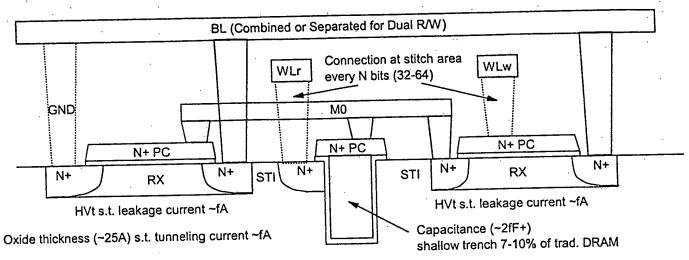




Vt\_gd

Vt\_rg Vg\_i





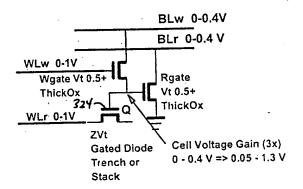
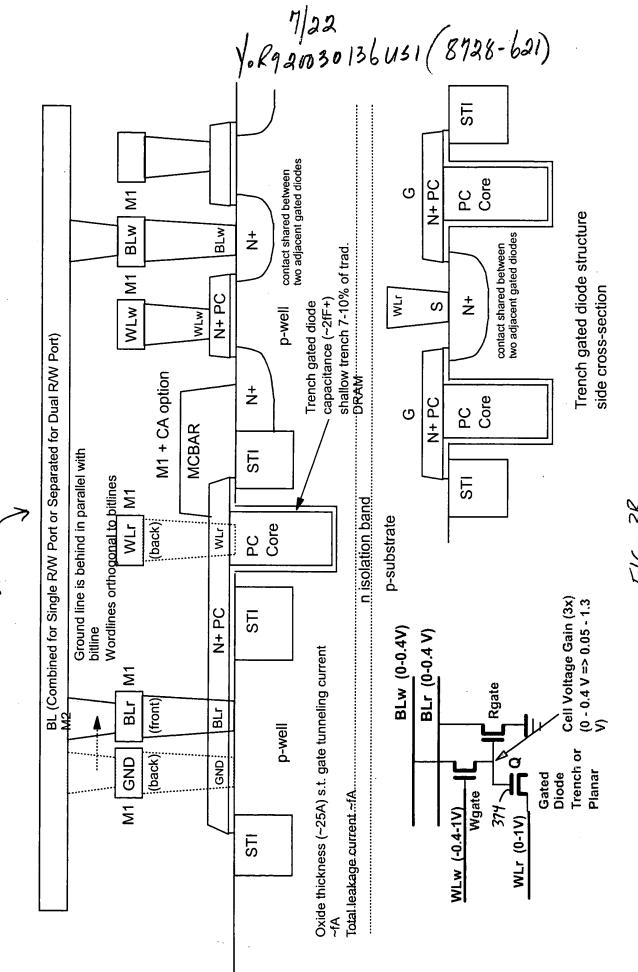
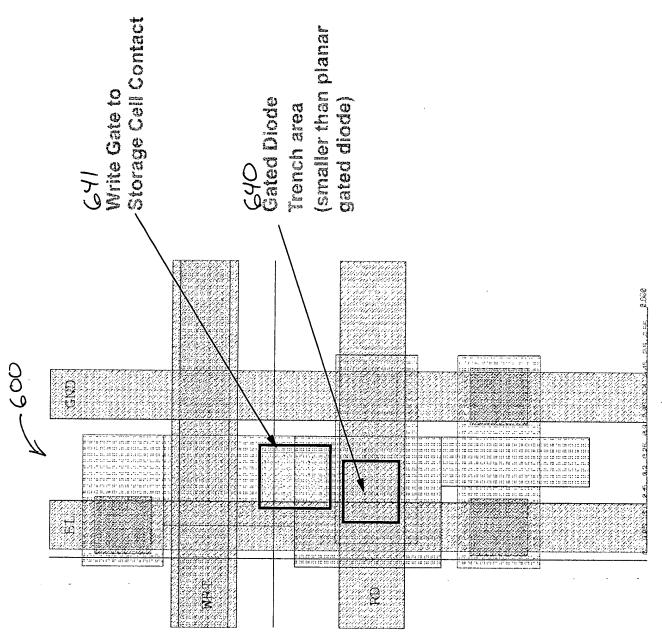


FIG. 3A



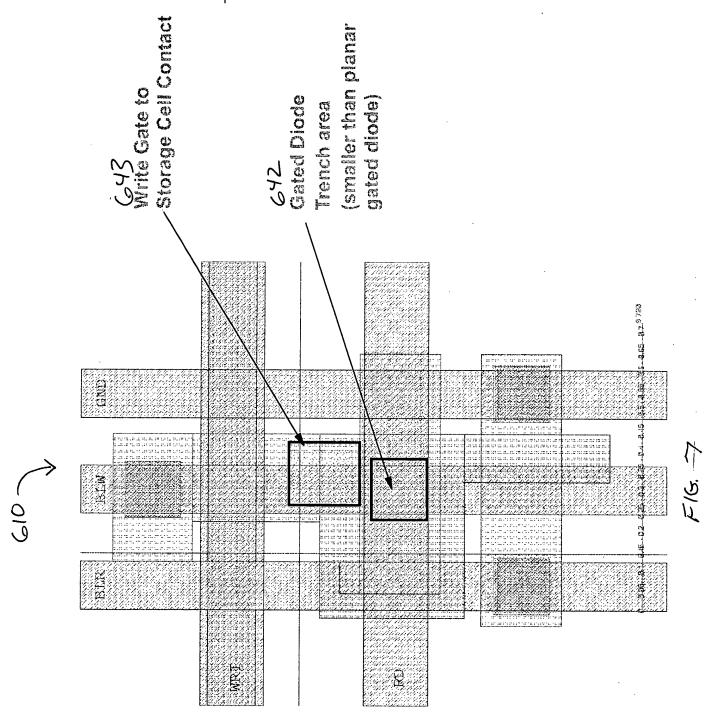
F16. 38

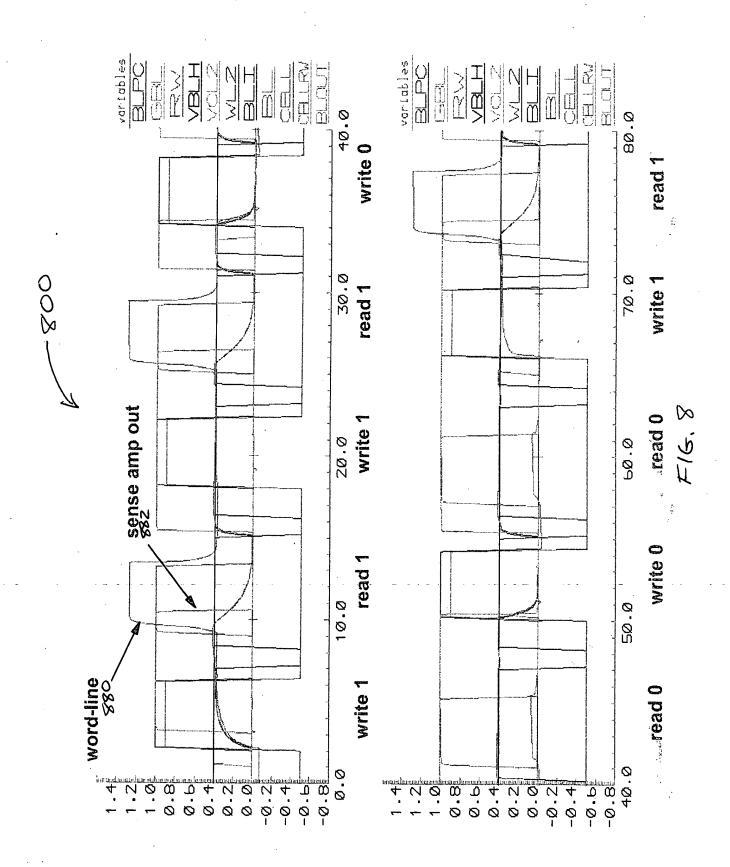
9/22 10R920136USI(8728-621) two adjacent gated diodes p-well contact shared between Σ BLw BLW ż WLw M1 N+ PC WLW BL (Combined for Single R/W Port or Separated for Dual R/W Port) M2 capacitance (~0.5-2fF) ż M1 + CA option Planar gated diode Ground line is behind in parallel with bitline MCBAR STI Wordlines orthogonal to bitlines WLr M1 n isolation band (optional) p-substrate (back) WL p-well (0 - 0.4 V => 0.05 - 1.3 V)462 Cell Voltage Gain (3x) N+ PC Oxide thickness (~25A) s.t. gate tunneling current ~fA BLw (0-0.4V) BLr (0-0.4 V) STI Σ Gated Diode BLr Trench or Planar (front) BLr 47% WLr (0-1V) Q p-well Wgate Total leakage current ~fA (back) GND WLw (-0.4-1V) GND Ξ STI



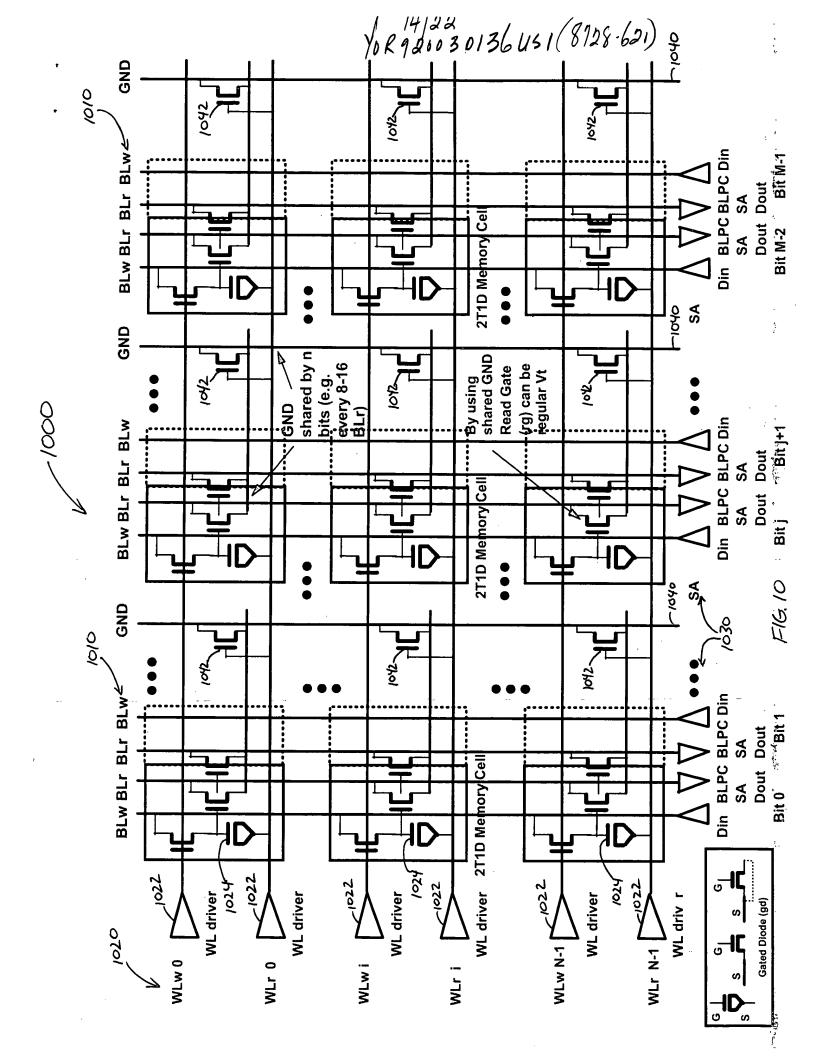
F/G 6

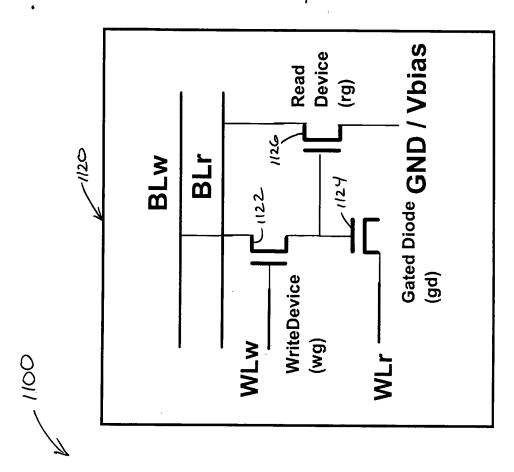
VoR92030136USI (8728-621)





13/22 1. R9 200 30136 USI (8728-621) BLw BLr Gnd BLr BLw Dout Bit M-2 2T1D Memory Cel BLW BLr Gnd BLr BLW BLPC Din SA Dout Bit j+1 Dout Bit j 2T1D Memory Cell 910 BLW BLr Gnd BLr BLW BLPC Din SA Dout Bit 1 WL driver 2T1D Memory|Cell 424 WL driver WL driver **WL** driver WL driver WL driver Gated Diode (gd) WLW N-1 WLr N-1





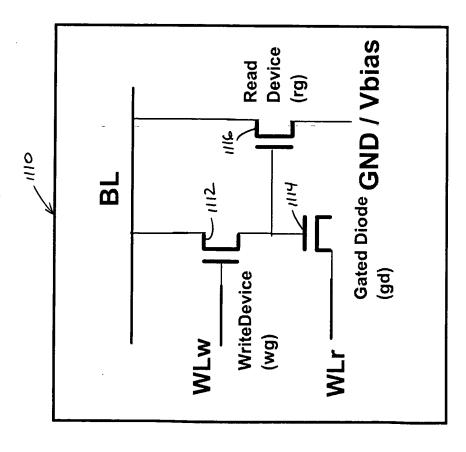
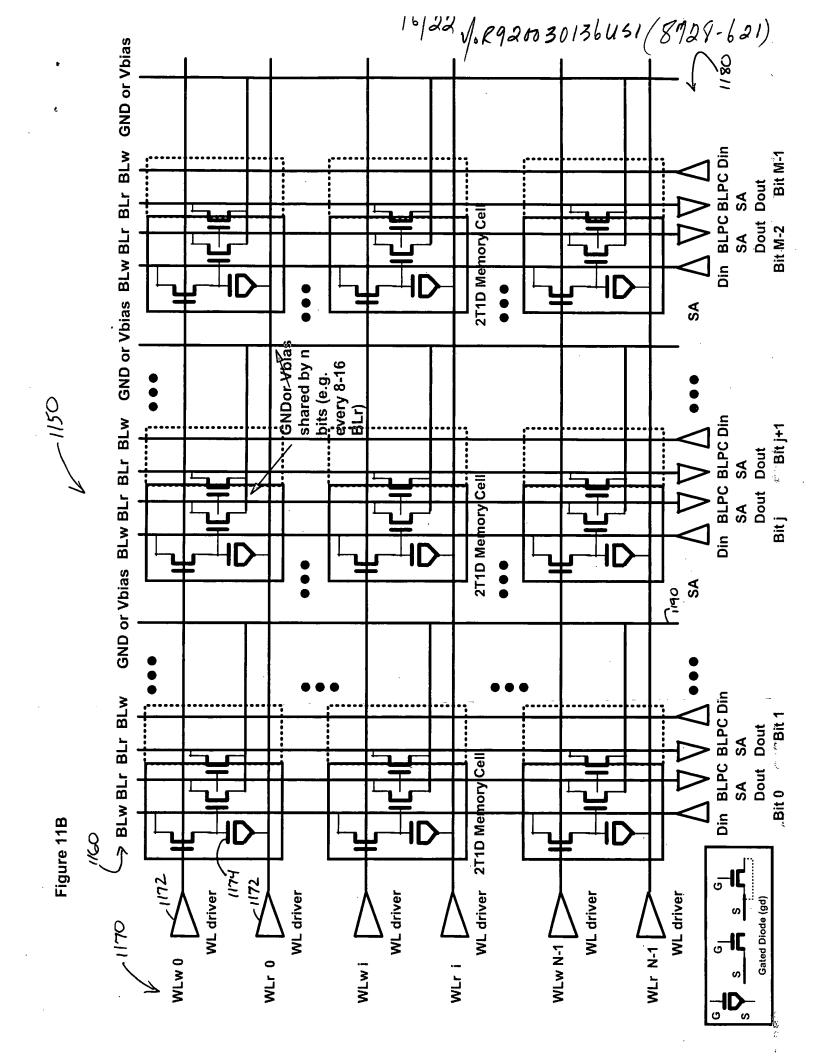
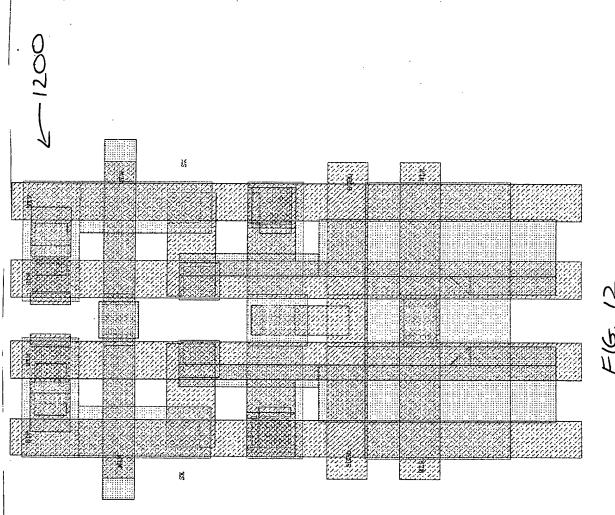
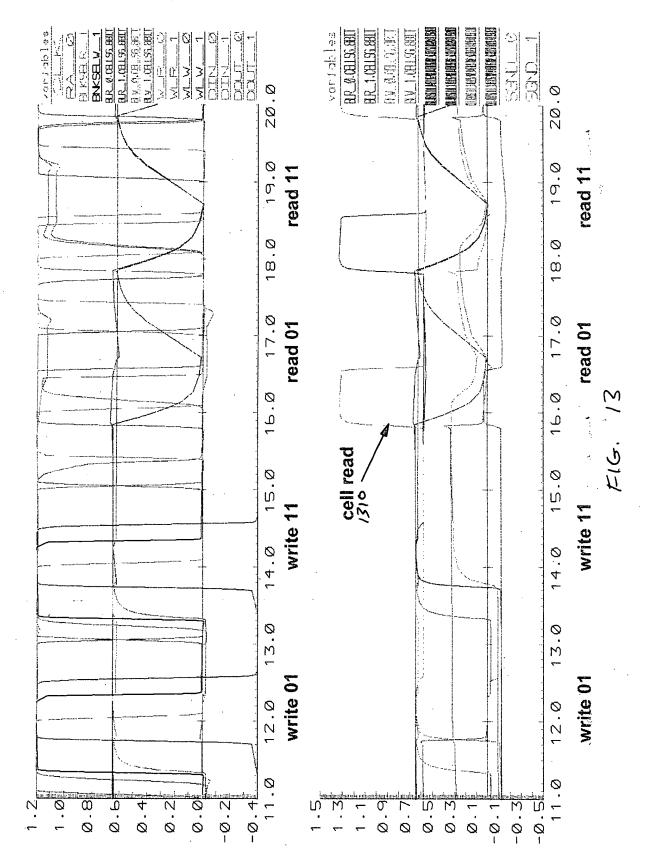


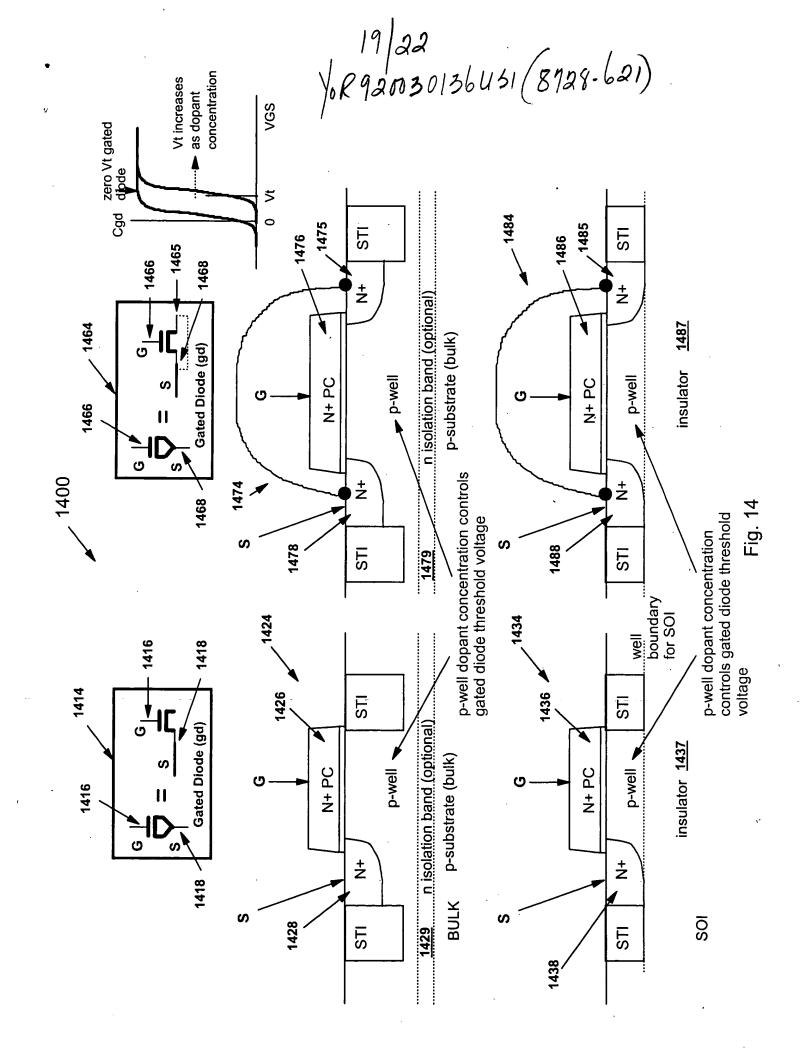
Figure 11A



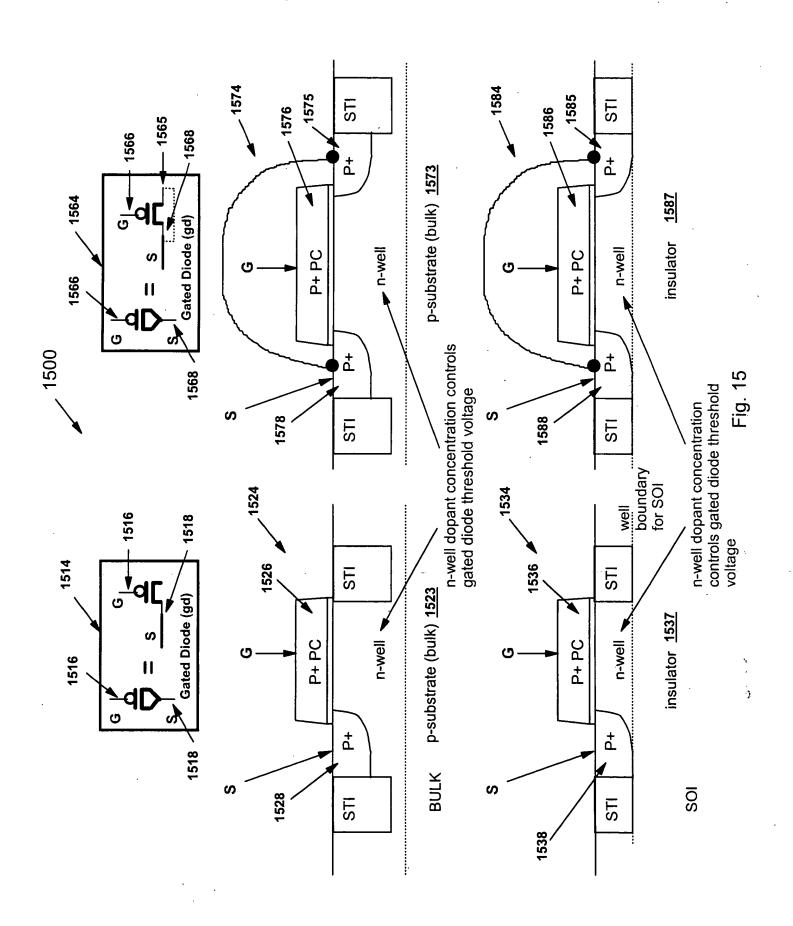




1300



## 20/22 Yo R921030136USI (8728-621)



1600

